

L Number	Hits	Search Text	DB	Time stamp
1	960	etch\$3 same silicide and ((CF4 "CF.sub.4" NF3 "NF.sub.3" SF6 "SF.sub.6") and (HCl Cl2 "Cl.sub.2") and (CO H2 "H.sub.2" N2 "N.sub.2"))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/03 20:44
2	210	etch\$3 same silicide and ((CF4 "CF.sub.4" NF3 "NF.sub.3" SF6 "SF.sub.6") same (HCl Cl2 "Cl.sub.2") same (CO H2 "H.sub.2" N2 "N.sub.2"))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/03 20:07
3	50	etch\$3 same silicide same ((CF4 "CF.sub.4" NF3 "NF.sub.3" SF6 "SF.sub.6") same (HCl Cl2 "Cl.sub.2") same (CO H2 "H.sub.2" N2 "N.sub.2"))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/03 20:07
4	20	etch\$3 same silicide same ((CF4 "CF.sub.4") same (Cl2 "Cl.sub.2") same (N2 "N.sub.2"))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/03 20:07
5	10	etch\$3 same silicide same ((CF4 "CF.sub.4") with (Cl2 "Cl.sub.2") with (N2 "N.sub.2"))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/03 20:08
6	8	etch\$3 with silicide same ((CF4 "CF.sub.4") with (Cl2 "Cl.sub.2") with (N2 "N.sub.2"))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/03 20:19
7	2	(etch\$3 same silicide same ((CF4 "CF.sub.4") with (Cl2 "Cl.sub.2") with (N2 "N.sub.2"))) not (etch\$3 with silicide same ((CF4 "CF.sub.4") with (Cl2 "Cl.sub.2") with (N2 "N.sub.2")))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/03 20:21
8	10	(etch\$3 same silicide same ((CF4 "CF.sub.4") same (Cl2 "Cl.sub.2") same (N2 "N.sub.2"))) not (etch\$3 same silicide same ((CF4 "CF.sub.4") with (Cl2 "Cl.sub.2") with (N2 "N.sub.2")))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/03 20:27
9	6	((etch\$3 same silicide same ((CF4 "CF.sub.4") same (Cl2 "Cl.sub.2") same (N2 "N.sub.2"))) not (etch\$3 same silicide same ((CF4 "CF.sub.4") with (Cl2 "Cl.sub.2") with (N2 "N.sub.2"))) and (sidewall passi\$7)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/03 20:31
10	30	(etch\$3 same silicide same ((CF4 "CF.sub.4" NF3 "NF.sub.3" SF6 "SF.sub.6") same (HCl Cl2 "Cl.sub.2") same (CO H2 "H.sub.2" N2 "N.sub.2"))) not (etch\$3 same silicide same ((CF4 "CF.sub.4") same (Cl2 "Cl.sub.2") same (N2 "N.sub.2")))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/03 20:31
12	0	(etch\$3 with silicide same ((CF4 "CF.sub.4" NF3 "NF.sub.3" SF6 "SF.sub.6") with (HCl Cl2 "Cl.sub.2") with (CO H2 "H.sub.2" N2 "N.sub.2"))) not (etch\$3 same silicide same ((CF4 "CF.sub.4" NF3 "NF.sub.3" SF6 "SF.sub.6") same (HCl Cl2 "Cl.sub.2") same (CO H2 "H.sub.2" N2 "N.sub.2")))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/03 20:45
11	16	etch\$3 with silicide same ((CF4 "CF.sub.4" NF3 "NF.sub.3" SF6 "SF.sub.6") with (HCl Cl2 "Cl.sub.2") with (CO H2 "H.sub.2" N2 "N.sub.2"))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/03 20:47

13	22	etch\$3 same silicide same ((CF4 "CF.sub.4" NF3 "NF.sub.3" SF6 "SF.sub.6") with (HCl Cl2 "Cl.sub.2") with (CO H2 "H.sub.2" N2 "N.sub.2"))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/03 20:47
14	6	(etch\$3 same silicide same ((CF4 "CF.sub.4" NF3 "NF.sub.3" SF6 "SF.sub.6") with (HCl Cl2 "Cl.sub.2") with (CO H2 "H.sub.2" N2 "N.sub.2"))) not (etch\$3 with silicide same ((CF4 "CF.sub.4" NF3 "NF.sub.3" SF6 "SF.sub.6") with (HCl Cl2 "Cl.sub.2") with (CO H2 "H.sub.2" N2 "N.sub.2")))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/03 20:47

L Number	Hits	Search Text	DB	Time stamp
1	750	etch\$3 same (SiO2 "SiO.sub.2" Si3N4 "Si.sub.3 N.sub.4" silicon adj (oxide nitride)) and ((CF4 "CF.sub.4" NF3 "NF.sub.3" SF6 "SF.sub.6") same (HCl Cl2 "Cl.sub.2") same (CO H2 "H.sub.2" N2 "N.sub.2" passi\$7))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/03 21:05
2	593	etch\$3 with (SiO2 "SiO.sub.2" Si3N4 "Si.sub.3 N.sub.4" silicon adj (oxide nitride)) and ((CF4 "CF.sub.4" NF3 "NF.sub.3" SF6 "SF.sub.6") same (HCl Cl2 "Cl.sub.2") same (CO H2 "H.sub.2" N2 "N.sub.2" passi\$7))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/03 21:10
3	104	etch\$3 with (SiO2 "SiO.sub.2" Si3N4 "Si.sub.3 N.sub.4" silicon adj (oxide nitride)) same ((CF4 "CF.sub.4" NF3 "NF.sub.3" SF6 "SF.sub.6") with (HCl Cl2 "Cl.sub.2") with (CO H2 "H.sub.2" N2 "N.sub.2" passi\$7))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/03 21:05
4	58	etch\$3 with (SiO2 "SiO.sub.2" Si3N4 "Si.sub.3 N.sub.4" silicon adj (oxide nitride)) with ((CF4 "CF.sub.4" NF3 "NF.sub.3" SF6 "SF.sub.6") with (HCl Cl2 "Cl.sub.2") with (CO H2 "H.sub.2" N2 "N.sub.2" passi\$7))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/03 21:10
5	15	etch\$3 with (SiO2 "SiO.sub.2" Si3N4 "Si.sub.3 N.sub.4" silicon adj (oxide nitride)) with ((CF4 "CF.sub.4") with (Cl2 "Cl.sub.2") with (N2 "N.sub.2"))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/03 21:09
6	43	(etch\$3 with (SiO2 "SiO.sub.2" Si3N4 "Si.sub.3 N.sub.4" silicon adj (oxide nitride)) with ((CF4 "CF.sub.4" NF3 "NF.sub.3" SF6 "SF.sub.6") with (HCl Cl2 "Cl.sub.2") with (CO H2 "H.sub.2" N2 "N.sub.2" passi\$7))) not (etch\$3 with (SiO2 "SiO.sub.2" Si3N4 "Si.sub.3 N.sub.4" silicon adj (oxide nitride)) with ((CF4 "CF.sub.4") with (Cl2 "Cl.sub.2") with (N2 "N.sub.2")))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/03 21:09